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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuhiko FUKAZAWA et al.

Group Art Unit: 2829

Application No.: 10/807,262

Examiner: J. NGUYEN

Filed: March 24, 2004

Docket No.: 119216

For: SUBSTRATE INSPECTION SYSTEM, SUBSTRATE INSPECTION METHOD, AND
SUBSTRATE INSPECTION APPARATUS

REQUEST FOR RECONSIDERATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the January 13, 2006 Office Action, Applicants request reconsideration of this application. Claims 1-17 are pending.

Claims 1-17 stand rejected under 35 U.S.C. §102(e) over U.S. Patent No. 4,644,172 to Sandland et al. This rejection is respectfully traversed.

Sandland et al. does not disclose or suggest the combinations of features recited in the independent claims of this application. Sandland et al. discloses a wafer inspection system that performs macro defect inspection and micro defect inspection. Whenever a wafer is inspected, the system of Sandland et al. first performs macro defect inspection and then performs micro defect inspection. See, for example, col. 6, lines 36-40 and col. 16, lines 53-61. While Sandland et al. indicates that it is not always necessary to inspect all wafers in a cassette (see, for example, col. 10, lines 17-19), whenever a wafer is inspected, both macro and micro defect inspection take place. Thus, Sandland et al. does not disclose or